

Supplementary Materials

Epitaxial growth of aligned MoS₂ via One-step CVD method for realizing the ultrasonic field-driven direct current nanogenerators

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Table S1. Comparison of aligned MoS₂ parameters prepared by CVD method

Annealing time	Carrier gas	Orientation rate (%)	Precursor consumption (MoO ₃)	Grain size	Ref.
1 h	Ar	Non-single orientation	6 mg	10-15 μm	1
4 h	Ar and O ₂	99	/	6-10 μm	2
4 h	Ar	86	/	60 μm	3
4 h	Ar	0° and 60°	30 mg	100 μm	4
6-20 h	Ar and H ₂ S	88	/	1-5 μm	5
4 h	Ar and O ₂	99	Mo sheets	30-50 μm	6
5 h	Ar and O ₂	/	Mo foil	20-30 μm	7
1 h	Ar	70	0.5 mg	100-200 μm	This work

Table S2 Some comparisons of TENG performance

Materials	Substrate or packaging material	current	Voltage	Charge	Energy source	Ref.
MoS ₂	Si/SiO ₂	200 nA	/	/	Ultrasonic waves	8
polymeric films	PDMS	/	26 V	/	Ultrasonic waves	9
Parylene	F-PCB	/	20 V	/	Ultrasonic waves	10

Continue table S2

Materials	Substrate or packaging material	current	Voltage	Charge	Energy source	Ref.
MoS ₂	Si ₃ N ₄ /Si	11 nA	7.3 V	/	moving NaCl droplet	11
PTFE	/	450 nA	15.6 V	4.5 nC	moving water droplet	12
PTFE	Si	10 μ A	79 V	576 nC	sliding gates	13
MoS ₂ /PTFE	Sapphire	1 mA	120 V	1200 nC	Ultrasonic waves	This work

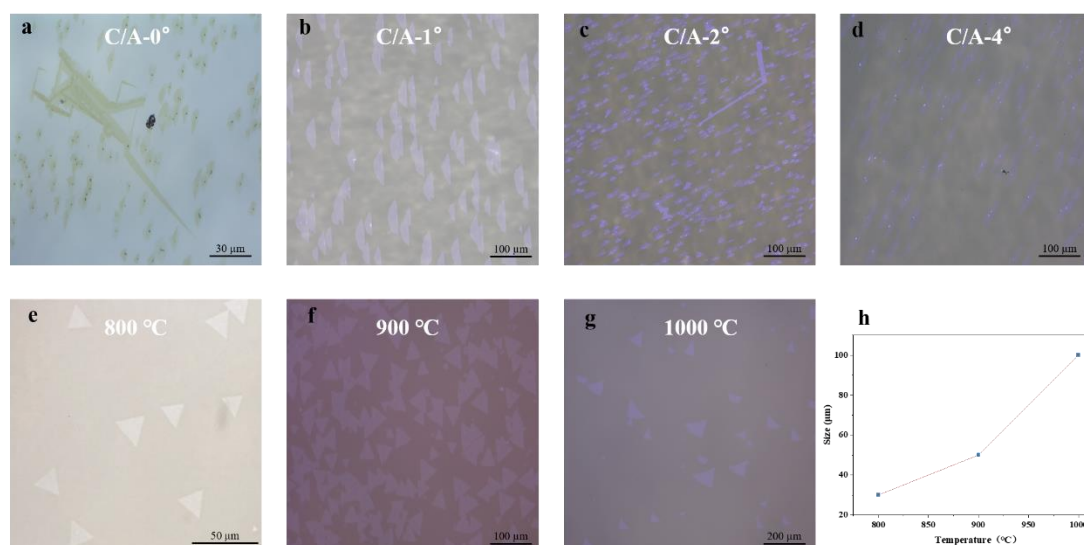


Figure S1. MoS₂ OM images of sapphire grown at different miscut angles (a-d). OM images of MoS₂ grown at different temperatures (e-g). The curve of MoS₂ grain size with temperature (h).

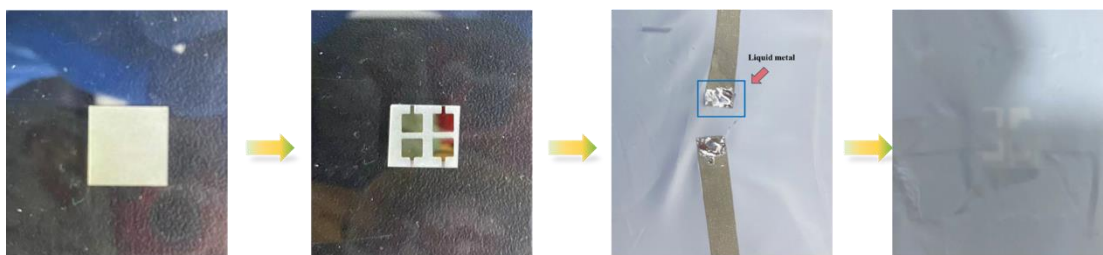


Figure S2 The photo of MoS₂-based TENG

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